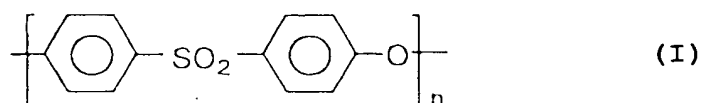


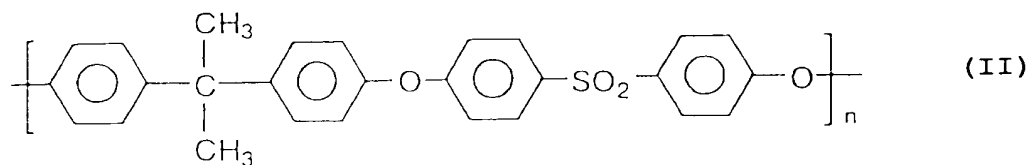
What is claimed is:

1. A filter cartridge for precision filtration comprising members of a micro-porous filtration membrane, a membrane support, a core, an outer cover and end plates, all of said members being made of polyether sulfone represented by formula (I):



wherein a reduced viscosity of pellets regenerated from said filter cartridge is not lower than 0.36 and lower than 0.45.

2. A filter cartridge for precision filtration comprising members of a micro-porous filtration membrane, a membrane support, a core, an outer cover and end plates, all of said members being made of polysulfone represented by formula (II):



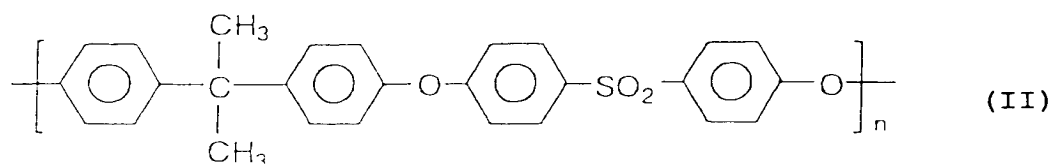
wherein a melt flow rate of pellets regenerated from said filter cartridge is not lower than 5.0 and lower than 9.0.

3. The filter cartridge for precision filtration as in Claim 1, wherein at least one of said members is formed by hot melt molding, and then subjected to annealing treatment.

4. The filter cartridge for precision filtration as in Claim 1, wherein said annealing treatment is carried out at a temperature of 140 to 200 °C for four hours or longer.

5. The filter cartridge for precision filtration as in Claim 1, wherein said cartridge assembled is cleaned with a dilute acid and with hot ultra-pure water having a temperature of from 50 °C to 100 °C.

6. A filtration method for semiconductor integrated circuit wafer cleaning fluid in a wafer cleaning process for manufacturing semiconductor integrated circuits, comprising the step of starting filtration of cleaning chemicals by use of a filter cartridge for precision filtration comprising members of a micro-porous filtration membrane, a membrane support, a core, an outer cover and end plates, all of said members being made of polysulfone represented by formula (II):



wherein a melt flow rate of pellets regenerated from said filter cartridge is not lower than 5.0 and lower than 9.0; without carrying out any preliminary hydrophilic treatment with alcohol.